

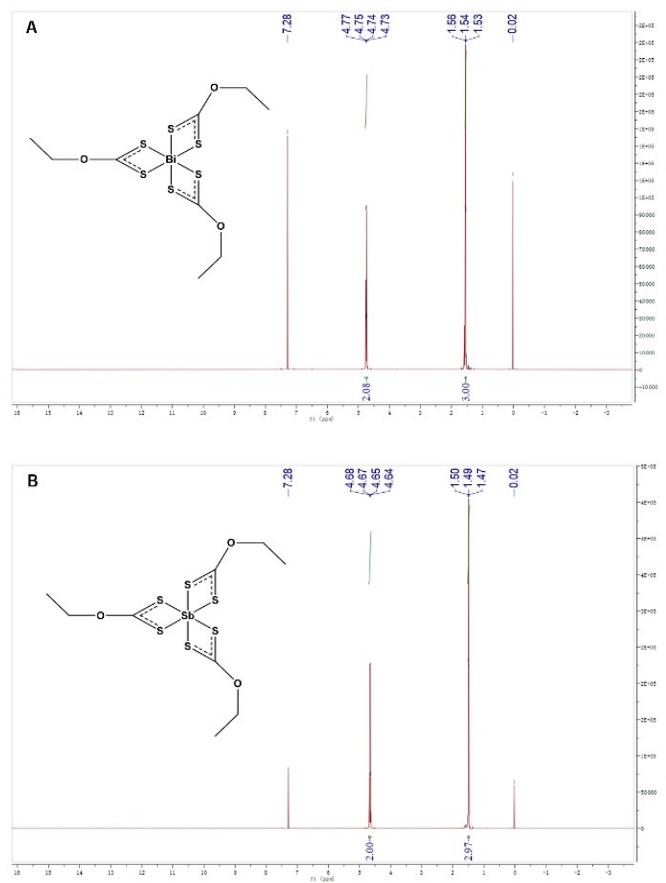
## Supporting Information

# Compositional Engineering of Metal-Xanthate Precursors toward $(Bi_{1-x}Sb_x)_2S_3$ ( $0 \leq x \leq 0.05$ ) Films with Enhanced Room-Temperature Thermoelectric Performance

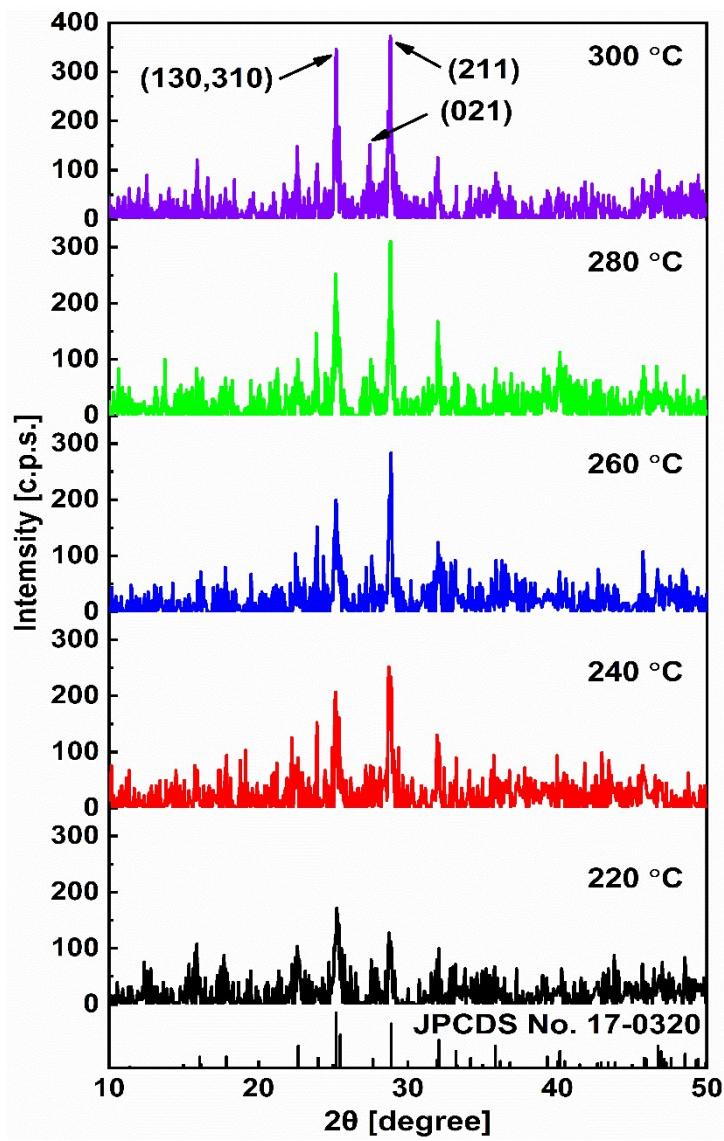
Zhenyu-Hu<sup>1,2,3</sup>, Longhui-Deng<sup>2,3</sup>, Tingjun-Wu<sup>3</sup>, Jing Wang<sup>4</sup>, Feiyan-Wu<sup>4</sup>, Lie Chen<sup>4</sup>, Qikai-Li,<sup>5</sup> Weishu-Liu<sup>5</sup>, Shui-Yang Lien<sup>6</sup>, Peng Gao<sup>2,3\*</sup>

1. College of Chemistry, Fuzhou University, Fuzhou, Fujian, 350108, China
2. CAS Key Laboratory of Design and Assembly of Functional Nanostructures, Fujian Provincial Key Laboratory of Nanomaterials, Fujian Institute of Research on the Structure of Matter, Chinese Academy of Sciences, 155 Yangqiao Road West, Fuzhou 350002, China
3. Xiamen Institute of Rare Earth Materials, Xiamen Key Laboratory of Rare Earth Photoelectric Functional Materials, Chinese Academy of Sciences, Xiamen 361021, China
4. College of Chemistry, Nanchang University, 999 Xuefu Avenue, Nanchang 330031, China.
5. Department of Materials Science and Engineering, Southern University of Science and Technology, Shenzhen 518055, China.
6. School of Opto-electronic and Communication Engineering, Xiamen University of Technology, Xiamen 361024, China

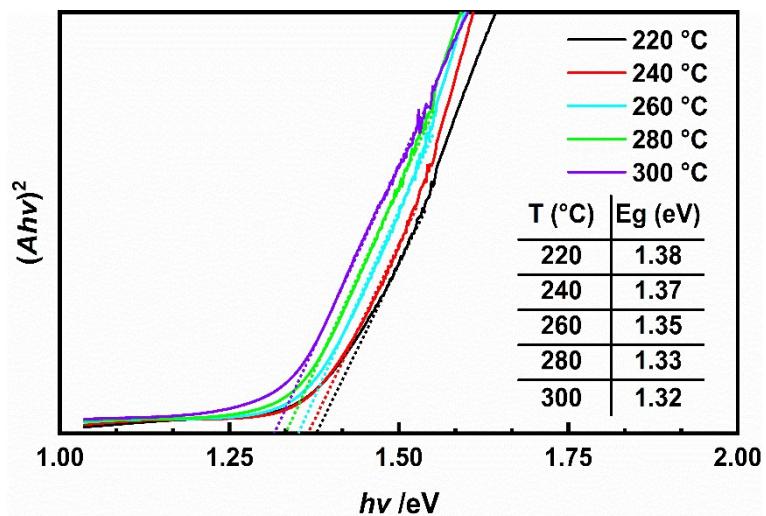
\*Corresponding author. E-mail address: peng.gao@fjirsm.ac.cn



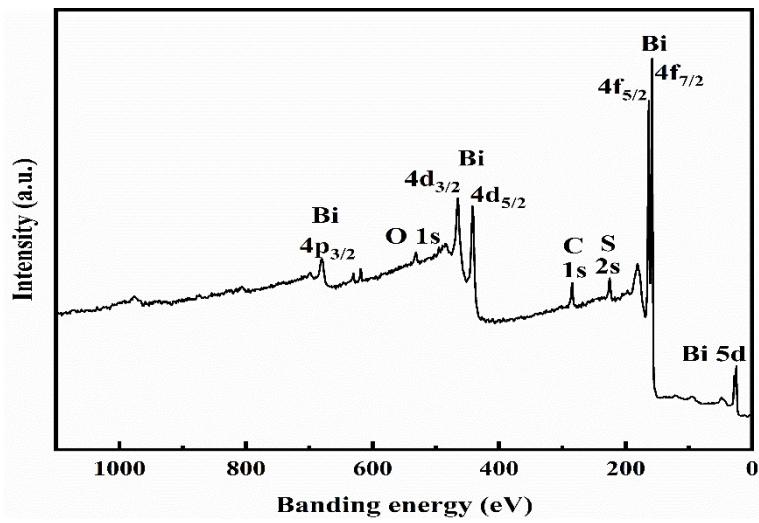
**Figure. S1** A and B are the  $^1\text{H}$  NMR spectrum of  $\text{Bi}(\text{S}_2\text{COEt})_3$  and  $\text{Sb}(\text{S}_2\text{COEt})_3$  in  $\text{CDCl}_3$ .



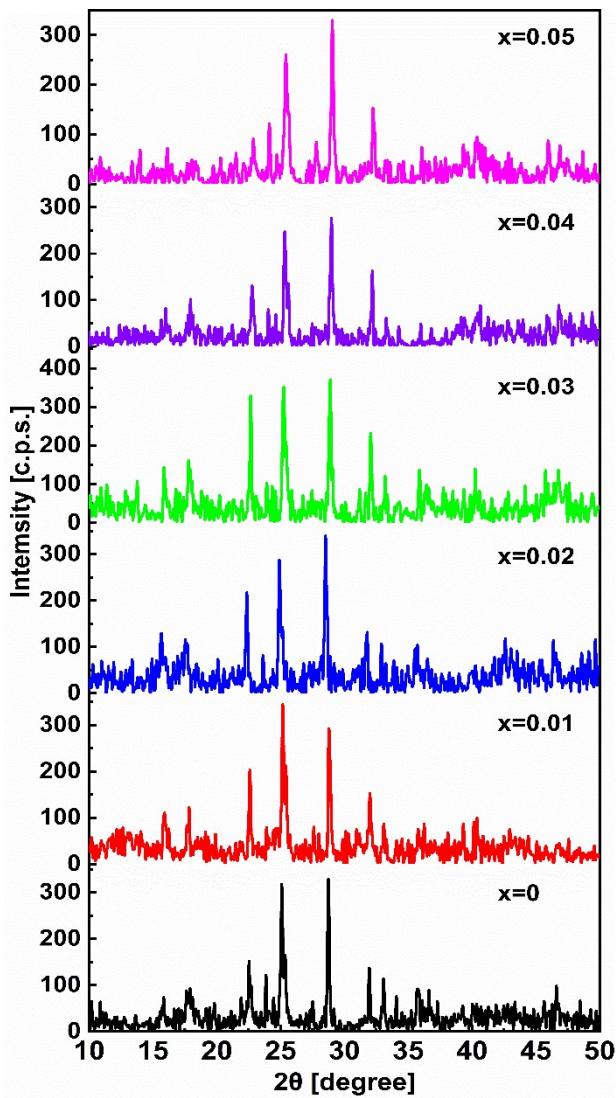
**Figure. S2** XRD pattern of  $\text{Bi}_2\text{S}_3$  thin films annealing at 220 °C, 240 °C, 260 °C, 280 °C, 300 °C.



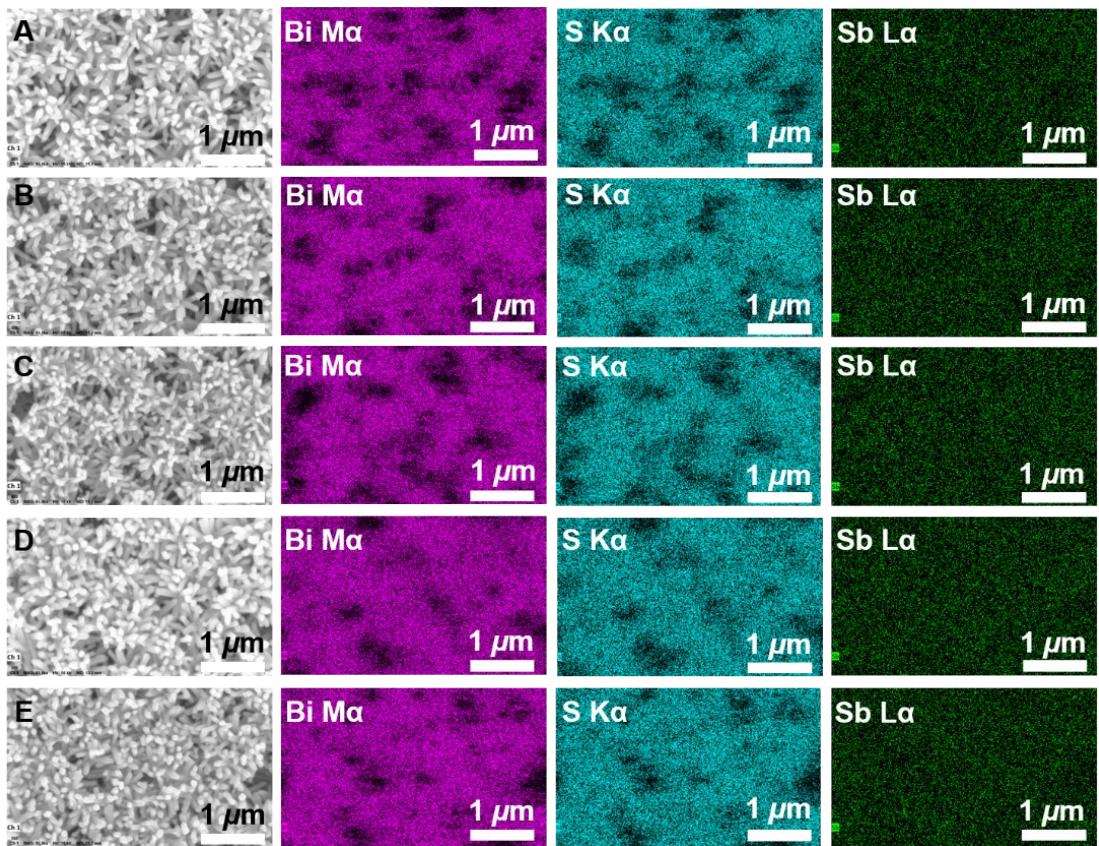
**Figure. S3** Temperature dependence of Tauc plot spectra for  $\text{Bi}_2\text{S}_3$  thin films.



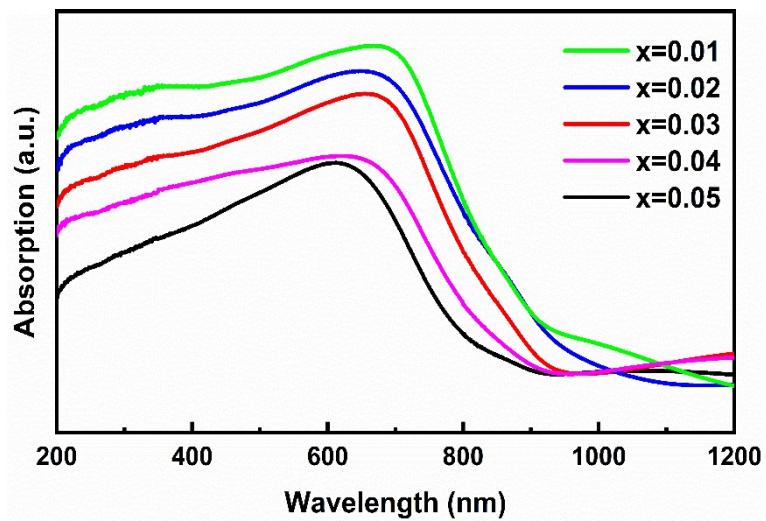
**Figure. S4** XPS survey spectrum of a pristine  $\text{Bi}_2\text{S}_3$  film annealed at 300 °C.



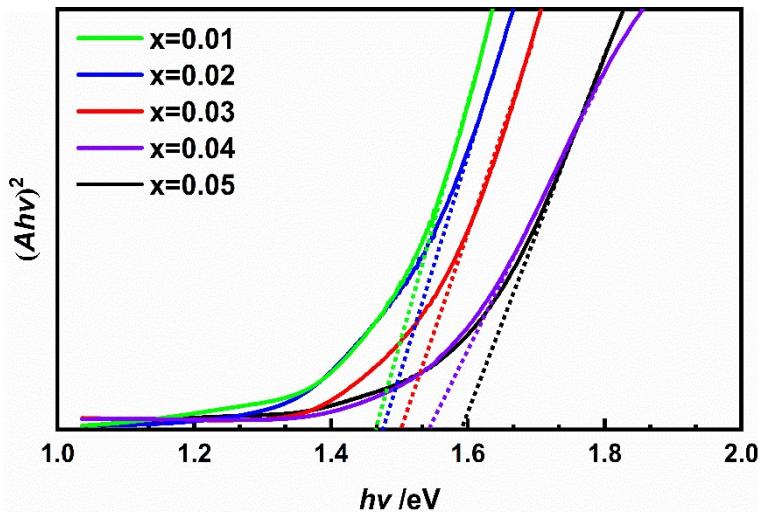
**Figure. S5** XRD pattern of  $(\text{Bi}_{1-x}\text{Sb}_x)_2\text{S}_3$  ( $0 \leq x \leq 0.05$ ) films annealed at 300 °C



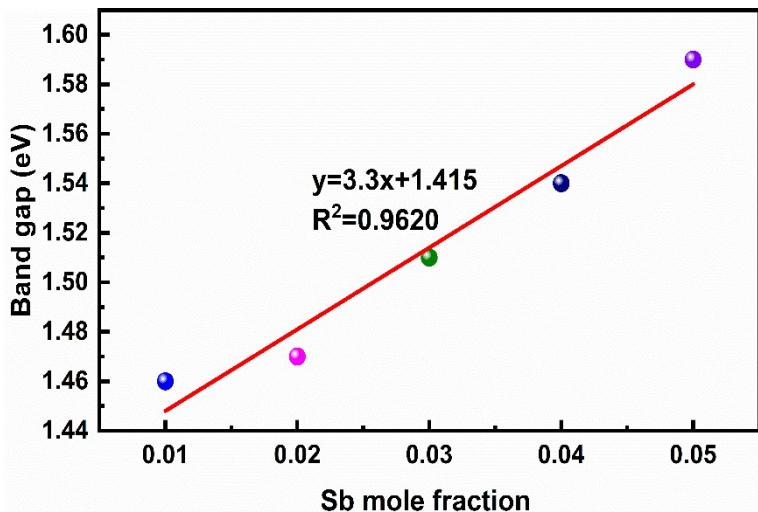
**Figure. S6** Energy Dispersive Spectrometer (EDX) elemental mapping (10 kV) of Bi Ma, Sb La and S K $\alpha$  for  $(\text{Bi}_{1-x}\text{Sb}_x)_2\text{S}_3$  samples. (A)  $x = 0.01$ , (B)  $x = 0.02$ , (C)  $x = 0.03$ , (D)  $x = 0.04$  and (E)  $x=0.05$  mole fractions of antimony.



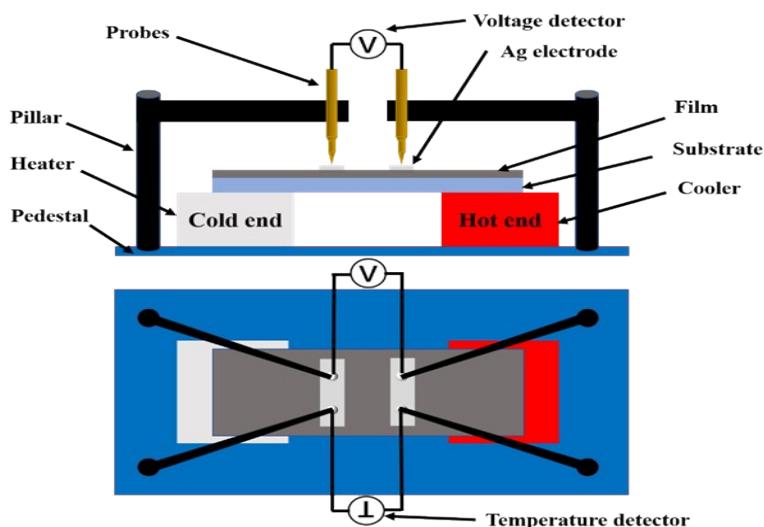
**Figure. S7** Absorption spectra of  $(\text{Bi}_{1-x}\text{Sb}_x)_2\text{S}_3$  ( $0.01 \leq x \leq 0.05$ ).



**Figure. S8** Tauc plot for the  $(\text{Bi}_{1-x}\text{Sb}_x)_2\text{S}_3$  ( $0.01 \leq x \leq 0.05$ )



**Fig. S9** Variation of the band gap for  $(\text{Bi}_{1-x}\text{Sb}_x)_2\text{S}_3$  ( $0.01 \leq x \leq 0.05$ ) samples as a function of mole fraction (x) of Sb.



**Figure. S10** Schematic of home-made for Seebeck coefficient measurement; above is the positive view, below is top view.

**Table S1** The thickness of Bi<sub>2</sub>S<sub>3</sub> film measured by surface stylus profiler.

Concentration (mol L <sup>-1</sup> )	Thickness (nm)
0.15	117.4
0.2	160.6
0.25	196.9
0.3	260.9

**Table S2** The lattice parameter of *a*-, *b*- and *c* axis and crystalline analysis about (Bi<sub>1-x</sub>Sb<sub>x</sub>)<sub>2</sub>S<sub>3</sub> (0≤x≤0.05) solid solution series.

Lattice axis (Å)	<i>a</i>	Sb mole fraction (x)					
		0	0.01	0.02	0.03	0.04	0.05
Lattice axis (Å)	<i>a</i>	11.1500	11.1533	11.1566	11.1589	11.1612	11.1639
Lattice axis (Å)	<i>b</i>	11.3489	11.3566	11.3697	11.3770	11.3849	11.3931
Lattice axis (Å)	<i>c</i>	3.9724	3.9626	3.9567	3.9483	3.9390	3.9317
Crystalline analysis	<i>V</i> (nm <sup>3</sup> )	502.664	501.917	501.896	501.256	500.525	500.079
Crystalline analysis	<i>D</i> (nm)	96.8762	78.9706	64.4241	45.9183	38.4402	36.3471
Crystalline analysis	$\delta$ ( $\times 10^{14}$ nm <sup>-2</sup> )	1.0655	1.6035	2.4094	4.7427	6.7675	7.5694
Crystalline analysis	$N$ ( $\times 10^{16}$ nm <sup>-2</sup> )	1.5983	2.4053	3.6141	7.1141	10.1513	11.3541

#Note: XRD calculation of (Bi<sub>1-x</sub>Sb<sub>x</sub>)<sub>2</sub>S<sub>3</sub> (0≤x≤0.05) films

(1). The volume of the cell was estimated using the equation

$$V = abc$$

(2). The crystallite size was decided using Scherrer equation

$$D = \frac{K\gamma}{B\cos\theta}$$

$K=0.89$  is Scherrer's constant;  $B$  is the FWHM of the diffraction peak of the measured sample;  $\theta$  is Bragg diffraction angle;  $\gamma$  is wavelength of X-ray, generally 1.5406 Å.

(3) Dislocation density of thin films can be determined using the equation <sup>1</sup>

$$\delta = 1/D^2$$

(4) Number of crystallites/unit area can be obtained using relationship <sup>2</sup>

$$N = t/D^3$$

 $t$  is the thickness of thin films.

**Table. S3** Annealing temperature dependences of the carrier transport properties of Bi<sub>2</sub>S<sub>3</sub> thin films, 5 samples were collected for each variable

Annealing temperature (°C)	Sample (#)	n ( $\times 10^{19}$ cm <sup>-3</sup> )	Mean/variance	$\mu$ (cm <sup>2</sup> V <sup>-1</sup> s <sup>-1</sup> )	Mean/variance	$\sigma_h^a$ (S cm <sup>-1</sup> )	Mean/variance
220	#1	2.215		1.204		4.273	
	#2	2.193		1.235		4.339	
	#3	2.510	2.291/	1.069	1.184	4.297	4.340/
	#4	2.301	0.128	1.238	/0.069	4.564	0.131
	#5	2.238		1.179		4.228	
240	#1	1.455		2.907		6.777	
	#2	1.503		2.867		6.904	
	#3	1.402	1.463/	3.045	2.900/	6.840	6.798/
	#4	1.442	0.045	2.746	0.108	6.344	0.285
	#5	1.513		2.939		7.124	
260	#1	0.807		7.445		9.626	
	#2	1.010		7.195		11.643	
	#3	0.912	0.885/	7.328	7.297/	10.708	10.353/
	#4	0.813	0.083	7.110	0.142	9.261	0.940
	#5	0.887		7.409		10.529	
280	#1	0.781		11.271		14.103	
	#2	0.785		11.391		14.326	
	#3	0.753	0.779	11.399	11.4/	13.752	14.227/
	#4	0.813	/0.023	11.403	0.094	14.853	0.405
	#5	0.763		11.536		14.102	
300	#1	0.198		45.268		14.360	
	#2	0.207		45.019		14.930	
	#3	0.189	0.196/	45.951	45.576/	13.914	14.305/
	#4	0.202	0.010	45.308	0.546	14.663	0.522
	#5	0.184		46.336		13.659	

<sup>a</sup> The electrical conductivity ( $\sigma_h$ ) calculated by  $\sigma = ne\mu$ .

<sup>b</sup> The electrical conductivity ( $\sigma_f$ ) measured with a four-point probe technique.

**Table. S4** Concentration of precursor dependences of the carrier transport properties of Bi<sub>2</sub>S<sub>3</sub> thin films, 5 samples are collected for each variable.

Concentration (mol L <sup>-1</sup> )	Sample (#)	n (×10 <sup>19</sup> cm <sup>-3</sup> )	Mean/ variance	μ (cm <sup>2</sup> V <sup>-1</sup> s <sup>-1</sup> )	Mean/ variance	σ <sub>h</sub> <sup>a</sup> (S cm <sup>-1</sup> )	Mean/ variance
0.15	#1	0.197		8.837		2.789	
	#2	0.195		8.490		2.653	
	#3	0.189	0.1918/	8.755	8.839/	2.651	2.712/
	#4	0.197	0.006	8.424	0.506	2.659	0.080
	#5	0.181		9.691		2.810	
0.2	#1	0.443		13.90		9.868	
	#2	0.332		15.298		8.137	
	#3	0.431	0.428/	14.970	14.239/	10.337	9.708/
	#4	0.434	0.061	13.772	0.873	9.576	0.967
	#5	0.502		13.207		10.622	
0.25	#1	1.036		5.041		8.367	
	#2	0.847		4.940		6.703	
	#3	0.929	0.958/	5.154	5.075/	7.671	7.793/
	#4	0.951	0.077	5.205	0.10	7.930	0.671
	#5	1.028		5.037		8.296	
0.3	#1	1.265		3.299		6.686	
	#2	1.372		3.488		7.667	
	#3	1.308	1.328/	3.254	3.260/	6.819	6.951/
	#4	1.425	0.068	2.970	0.189	6.780	0.403
	#5	1.273		3.337		6.806	

<sup>a</sup> The electrical conductivity (σ<sub>h</sub>) calculated by  $\sigma = ne\mu$ .

<sup>b</sup> The electrical conductivity (σ<sub>f</sub>) measured with a four-point probe technique.

**Table S5** Sb mole fraction dependences of the carrier transport properties of Bi<sub>2</sub>S<sub>3</sub> thin films, 5 samples are collected for each variable.

Sb mole fraction	Sample (#)	n ( $\times 10^{19}$ cm <sup>-3</sup> )	Mean/variance	$\mu$ (cm <sup>2</sup> V <sup>-1</sup> s <sup>-1</sup> )	Mean/variance	$\sigma_h^a$ (S cm <sup>-1</sup> )	Mean/variance
0.01	#1	0.250		6.531		2.616	
	#2	0.216		6.088		2.107	
	#3	0.247	0.247/0.019	6.664	6.461/0.291	2.637	2.566/0.298
	#4	0.270		6.785		2.935	
	#5	0.254		6.241		2.540	
0.02	#1	0.279		9.188		4.107	
	#2	0.326		8.844		4.619	
	#3	0.204	0.271/0.044	10.366	9.56/0.633	3.388	4.130/0.455
	#4	0.265		10.067		4.274	
	#5	0.285		9.341		4.265	
0.03	#1	0.378		14.450		8.751	
	#2	0.384		14.390		8.853	
	#3	0.362	0.380/0.017	14.989	14.409/0.474	8.693	8.776/0.118
	#4	0.371		14.545		8.646	
	#5	0.408		13.671		8.937	
0.04	#1	0.541		3.260		2.826	
	#2	0.478		3.805		2.914	
	#3	0.502	0.514/0.031	3.120	3.364/0.260	2.510	2.764/0.173
	#4	0.496		3.356		2.667	
	#5	0.553		3.280		2.906	
0.05	#1	1.851		0.714		2.117	
	#2	1.690		0.779		2.108	
	#3	1.773	1.831/0.105	0.716	0.745/0.039	2.034	2.187/0.189
	#4	1.967		0.798		2.516	
	#5	1.875		0.720		2.163	

<sup>a</sup> The electrical conductivity ( $\sigma_h$ ) calculated by  $\sigma = ne\mu$ .

<sup>b</sup> The electrical conductivity ( $\sigma_f$ ) measured with a four-point probe technique.

**Table S6** Electrical resistivity( $\sigma$ ), Seebeck coefficient, and power factor for the  $\text{Bi}_2\text{S}_3$  films in present work and other typical TE films at room temperature.

Method	Sample	$\sigma$ ( $\text{S}\cdot\text{cm}^{-1}$ )	Seebeck ( $\mu\text{V}\cdot\text{K}^{-1}$ )	PF ( $\mu\text{W}\cdot\text{m}^{-1}\cdot\text{K}^2$ )	Ref.
Spin-coating and annealing	$\text{Bi}_2\text{S}_3$ films	10.32	-388.33	155.63	This work
Melting and Spark plasma sintering (SPS)	$\text{Bi}_2\text{S}_3$ bulk	4	-352	49.56	3
Nanocomposite pellet	$\text{Bi}_2\text{S}_3@\text{Bi}$ bulk	39.65	-97.38	37.66	4
SPS	$\text{Bi}_2\text{S}_3@\text{Bi}$ bulk	38.89	~-150	~87.50	5
Melting and SPS	$(\text{Bi}_{0.2}\text{Sb}_{0.8})_2\text{S}_3$ bulk	$2.52\times 10^{-3}$	~-450	~0.05	6
Electron Beam and Spin-coating	$\text{Bi}_2\text{S}_3$ films	6.0	-21.41	0.28	7
Wet chemical synthesis	$\text{Bi}_2\text{S}_3$ films	$5\times 10^{-3}$	~-650	0.02	8
Chemical Bath Deposition	$\text{Bi}_2\text{S}_3$ films	50	-755	2850	9
Melting–SPS	$\text{Sb}_2\text{Se}_3$ whisker	~1	~-200	~2	10
SPS	$\text{Bi}_{1.995}\text{Cu}_{0.005}\text{S}_3$ bulk	14.41	~-275	~108.97	11

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